High Quality Ultra Thin CVD HfO_2 Gate Stack with Poly-Si Gate Electrode

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Abstract

We have developed and demonstrated an *in-situ* rapid thermal CVD (RTCVD) process for the fabrication of high quality ultra thin CVD HfO_2 gate stack that is compatible with conventional self-aligned poly-Si gate technology. These poly-Si gated HfO_2 gate stack show excellent interface properties, EOT=10.4Å, and leakage current Jg=0.23mA/cm^2 @Vg=-1V which is several orders of magnitude lower than RTO SiO_2 with poly-Si gate. In addition, the HfO_2 gate stack is thermally stable in direct contact with n^+-poly Si gate under typical dopant activation conditions. These films also show excellent reliability under high-field electrical stress. We have also fabricated and demonstrated NMOSFETs, and studied boron penetration in HfO_2 gate stack with p^+-poly Si gate.

Introduction

In an attempt to develop advanced gate dielectric film replacing SiO_2, many high-K materials have been investigated to meet the requirements for sub-100 nm technology. Key issues related to the development of high-K gate stack with conventional dual-gate poly-Si CMOS process are the thermal stability of high-K materials in direct contact with silicon and poly-Si at high temperatures, high quality interfaces with channel and gate electrode, reasonable barrier height to achieve low leakage current, and suppressed boron penetration. The compatibility of high-K gate stack with conventional poly-Si dual-gate CMOS process has received considerable attention. Recently, HfO_2 films have emerged as the most promising gate dielectric material for sub 100nm technology due to its superior thermal stability with poly-Si and reasonable band alignment [1], [2]. Kang et al. used PVD sputtered HfO_2 and poly-Si electrode to fabricate the MOS devices with the CET (Capacitance Equivalent Thickness) of 16.3Å and good leakage current [3].

In this paper, we report the electrical and chemical properties, thermal stabilities, reliability characteristics, and NMOSFET characteristics of ultra thin (EOT=10.4Å) CVD HfO_2 with conventional poly-Si gate process.

Experiment

The MOS capacitors used in our study with the HfO_2 gate stack were fabricated on Si substrates using an *in-situ* RTP multiprocessing whose process procedure is shown in Fig 1. After the standard RCA cleaning with final HF dip, the NH_3-based interface layer was grown at 700°C for 10sec. The CVD HfO_2 films were deposited at 500°C for 3min using O_2 and $C_{16}H_{36}HfO_4$ with N_2 as a carrier gas. The *in-situ* post-deposition annealing was performed in an N_2 ambient at 700~900°C for 30sec to improve the film quality and reduce the leakage current. The amorphous Si gate (~1600Å) was deposited directly on the HfO_2 at 540°C, followed by either $POCL_3$ doping at 900°C or ion implantation of Phosphorus for NMOS and BF_2 for PMOS. The gate dopants were activated at 900 ~ 1000°C for 30 ~ 60sec. The NMOSFETs were also fabricated with conventional self-aligned poly-Si gate process.

The EOT (Equivalent Oxide Thickness) is extracted from the simulation program considering quantum mechanical (QM) and poly-depletion effects. The chemical properties and thermal stability of ultra-thin HfO_2 gate stacks with poly-Si capping were investigated by an *in-situ* XPS (X-ray Photoelectron Spectroscopy) in an integrated CVD film growth and analysis system.

Results and Discussion

1. High quality HfO_2 gate stack with conventional n^+-poly Si gate process

The importance of the NH_3-based interface layer on the high-K dielectric to improve the interfacial properties and reduce the final EOT was reported in [4]. The NH_3-based interface layer provides strong resistance to oxidation of the silicon substrate during the CVD of HFO_2 and, more importantly, during the post-deposition annealing. It is found that N_2 post deposition annealing is very effective to improve the film quality and reduce the leakage current. By using these processes, we have achieved HfO_2 gate stack with EOT=10.4Å and

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$Jg=0.23mA/cm^2$ @Vg=-1V, as shown in Fig. 2. The negligible difference between the measured HFCV and the simulated LFCV and a smooth transition in depletion region indicate extremely low interface state density. The flat band voltage of n^+-poly Si-gated HfO_2 gate stack is -0.8V, which is similar to that of the SiO_2 with n^+-poly Si gate and the same substrate doping concentration. The HfO_2 gate stack with n^+-poly Si gate shows $>10^4$ times lower leakage current @Vg=-1V than that of SiO_2 for EOT<15Å (Fig. 3).

The hysteresis characteristics in HFCV of the HfO_2 gate stack is compared with different gate electrode by monitoring the amounts of flat band voltage shift (Fig. 4). The V_{FB} shifts after 4 sweeps between ±2V for n^+-poly Si gate devices are extremely low: 2mV for $POCL_3$ doped and 5mV for P-implanted, compared to 32mV for TiN/Al gate, indicating hysteresis characteristics are strongly affected by gate material. These films also show negligible frequency dependence in HFCV (Fig. 5) over the range of 10kHz-1MHz, indicating negligible slow interface traps in HfO_2 gate stack.

The thermal stability of the CVD HfO_2 gate stack with n^+-poly Si gate is studied by monitoring the changes in both C-V and I-V of the gate stack as a function of several gate activation conditions (Fig. 6). As can be seen from Fig. 6, negligible changes in both C-V and I-V are observed, indicating that HfO_2 is thermally stable after 950°C anneal in direct contact with n^+-poly Si gate.

The thermal stability of CVD HfO_2 gate stack is also examined by *in-situ* XPS analysis in an integrated CVD film growth and surface analysis system. After the CVD of HfO_2 and N_2 post-deposition anneal, poly-Si was deposited at 600°C, followed by N_2 anneal at 900, 950°C. As shown in Fig. 7, CVD HfO_2 films remain stable after poly-Si deposition and annealing in UHV N_2 ambient up to 950°C, and show no evidence of the formation of undesirable Hf metal or Hf silicide phases. No changes in C-V and I-V were found after forming gas sintering (450°C, 30min) either. The HRXTEM of the HfO_2 gate stack with n^+-poly Si gate in Fig. 8 shows extremely thin interface layer below CVD HfO_2 and sharp interfaces, with HfO_2 film remaining amorphous after gate activation at 950°C for 60sec. The dielectric constant of the CVD HfO_2 layer is estimated to be 24.

2. Reliability, Boron penetration, and NMOSFET characteristics

The HfO_2 with n^+-poly Si gate displays fairly weak temperature dependence of the I-V characteristics (Fig. 9), indicating that trap-assisted conduction in this film is not the dominant mechanism. The reliability characteristics of HfO_2 gate stack was studied by investigating the SILC (Stress Induced Leakage Current) and charge trapping characteristics under constant voltage stress. The SILC was measured under negative constant voltage stress with E=16MV/cm. After applying stress for 1000sec, the increase of leakage current is negligible at low electric field (Vg=-0.5V) (Fig. 10(a)). The negligible charge trapping in HfO_2 gate stack is observed during constant voltage stress with E=16MV/cm (Fig. 10(b)). Under extremely high field stressing (E>20MV/cm), both soft and hard breakdown, as well as SILC could be seen. As a result, it is very difficult to obtain long-term TDDB on CVD HfO_2 gate stack. Fig. 11 shows boron penetration characteristics in p^+-poly HfO_2 gate stack on n-type Si substrates. Up to 1000°C, 10sec annealing, negligible flat band voltage shift was found, suggesting no boron penetration. However, upon 1000°C, 30sec annealing, boron penetration is observed. Fig. 12 shows Id-Vd characteristics of NMOSFET with HfO_2 gate stack and n^+-poly Si gate. Fig. 13 shows Id-Vg characteristics of HfO_2 with excellent sub-threshold swing of 73mV/dec

Summary

In this paper, we report ultra thin high quality CVD HfO_2 poly-Si gated stack with EOT=10.4Å and $Jg=0.23mA/cm^2$ @Vg=-1V. This film shows good interface properties, extremely small hysteresis (<5mV) and negligible frequency dependence in HFCV, and excellent reliability characteristics. The thermal stability of the HfO_2 with n^+-poly Si gate is confirmed by the electrical measurements, in-situ XPS analysis and the HRXTEM. NMOSFETs fabricated with HfO_2 gate stack demonstrate good drive current and excellent sub-threshold swing. Boron penetration in these films is also investigated. Our results suggest that CVD HfO_2 gate stack is very promising for possible direct insertion into standard dual-gate CMOS process.

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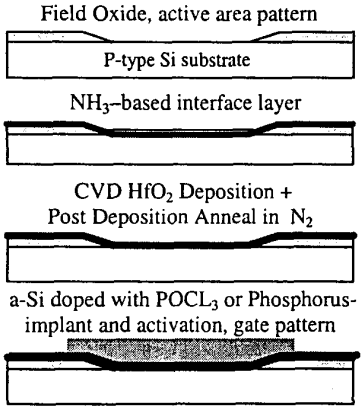

Fig. 1. In-situ RTP fabrication process for HfO_2 gate stack.

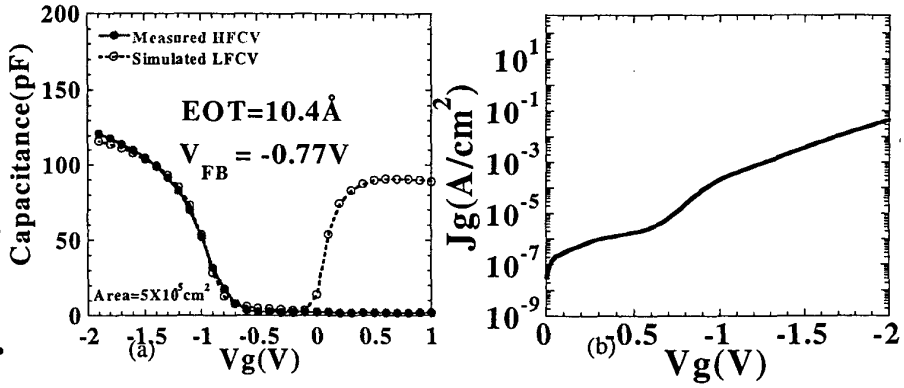

Fig. 2. (a) Measured HFCV and Simulated LFCV and (b) Jg-Vg of HfO_2 gate stack with a-Si gate doped with Phosphorus-implantation.

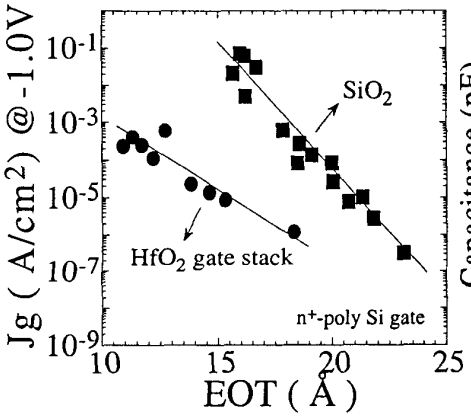

Fig. 3. Current density @ Vg=-1V as a function of EOT for HfO_2 and SiO_2 with n^+-poly Si gate.

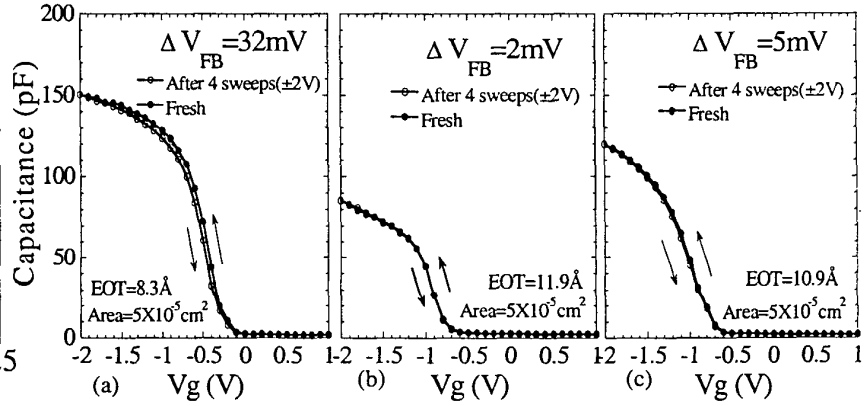

Fig. 4. Hystereis in HFCV of HfO_2 gate stack with (a)TiN/Al gate, (b)a-Si gate doped with $POCL_3$ (c)a-Si doped with Phosphorus-implantation.

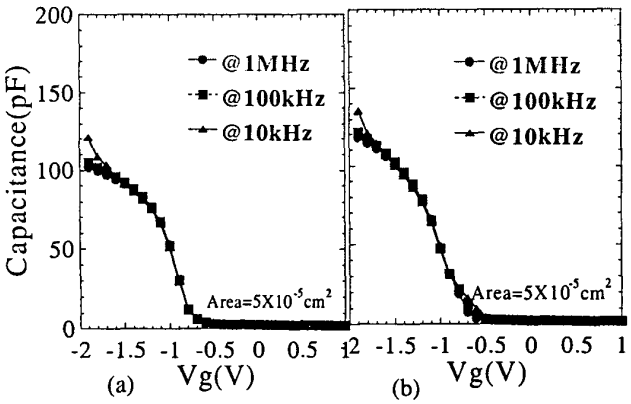

Fig. 5. Frequency dependence in HFCV of HfO_2 gate stack with (a)a-Si gate doped with $POCL_3$ (b)a-Si gate with Phosphorus-implantation.

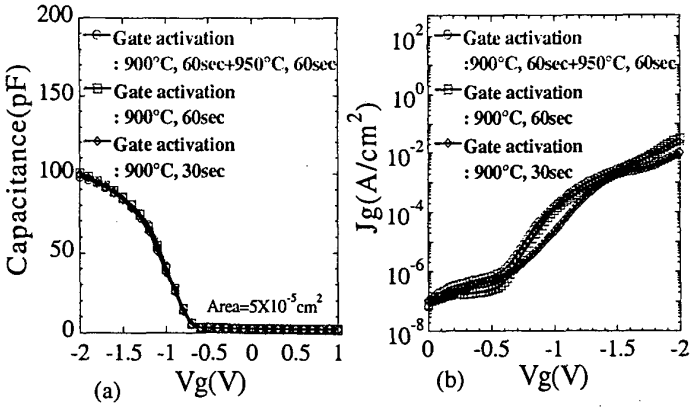

Fig. 6. Thermal stability of HfO_2 gate stack with n^+-poly Si gate : effects of different Phosphorus activation temperature and time on (a) HFCV and (b) Jg-Vg.

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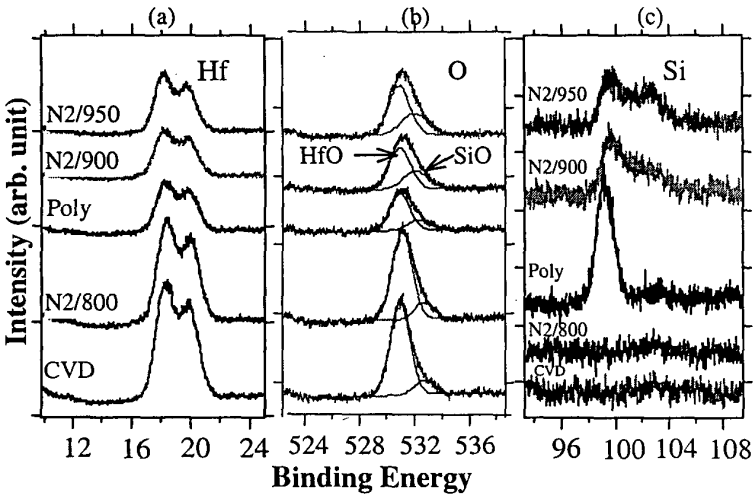

Fig. 7. XPS analysis of (a) Hf 4f, (b) O 1s and (c) Si 2p of HfO_2 gate stack deposited on clean Si(100) at 450°C for 2min followed by N_2 annealing at 800°C for 1min, poly-Si deposition at 600°C and N_2 annealing at 900°C and 950°C for 30sec.

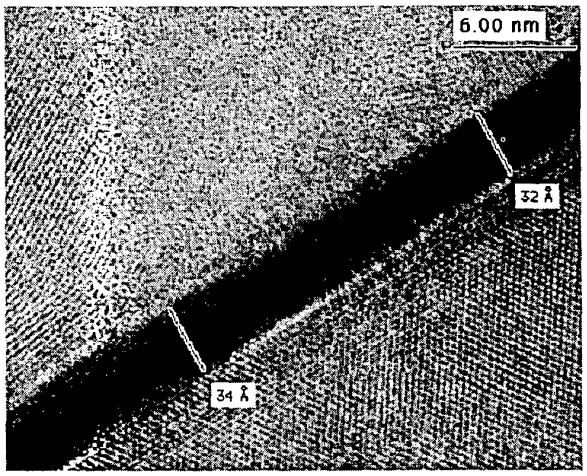

Fig. 8. TEM picture of HfO_2 gate stack with a-Si gate doped with P-implant (Gate Activation : 900°C, 60sec + 950°C, 60sec).

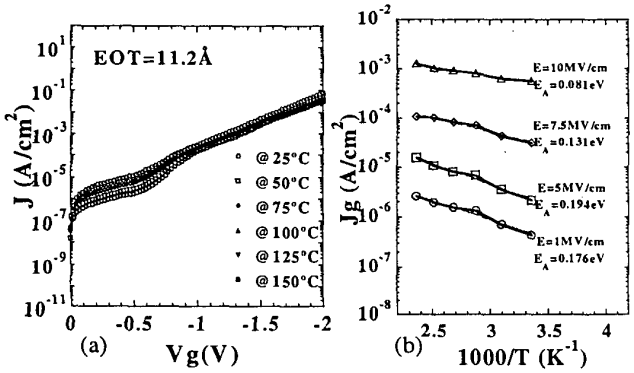

Fig. 9. (a) Jg-Vg at different temperature (b) Arrhenius's plot of temperature dependent leakage current of HfO_2 gate stack with a-Si gate doped with Phosphorus implantation.

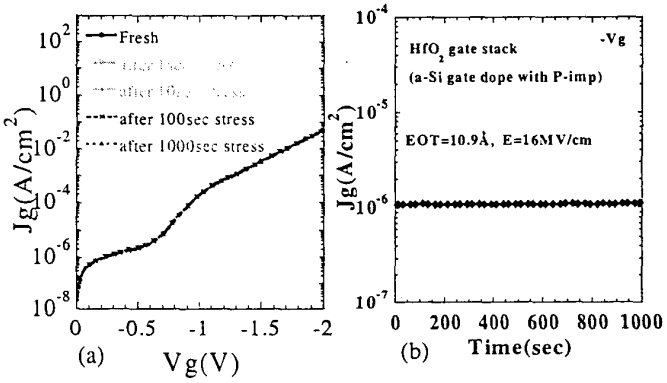

Fig. 10. (a) Jg-Vg after constant voltage stress (b) Jg-Time during during constant voltage stress of HfO_2 gate stack with a-Si gate doped with Phosphorus implantation.

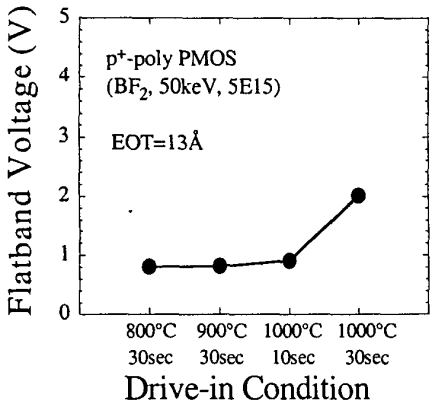

Fig. 11. Boron penetration characteristics of HfO_2 gate stack by flatband voltage shift during gate activation.

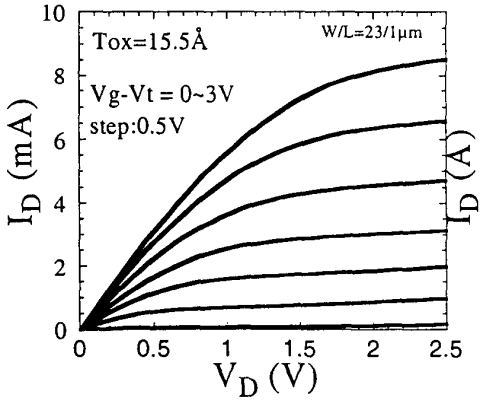

Fig. 12. Id-Vd characteristics of NMOSFET (HfO_2 gate stack with n^+-poly Si gate).

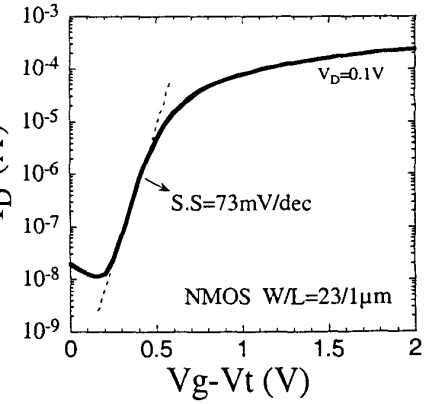

Fig. 13. Id-Vg characteristics of NMOSFET (HfO_2 gate stack with n^+-poly Si gate).

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